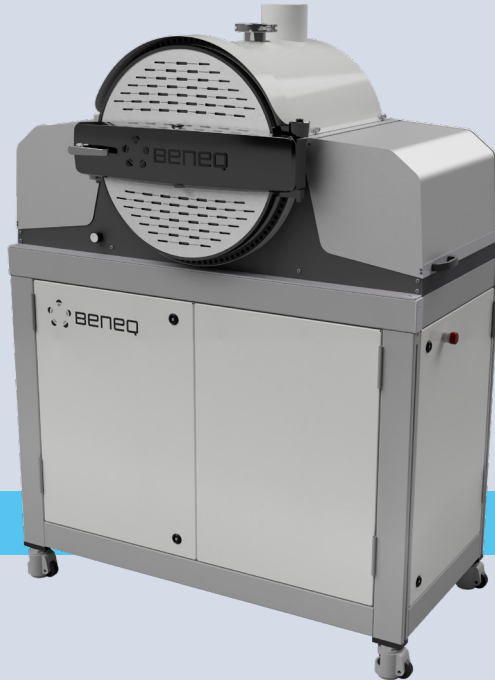


BENEQ R2



COMPACT. SCALABLE. PERFECT FOR YOUR
START WITH ALD

- A premium ALD reactor packaged in a compact enclosure.
- Ergonomically designed from the ground up with focus on performance and ease of use
- Modular design allows for quick upgrades and maintenance.

BENEQ R2

PROCESS TYPE

- Thermal ALD
- Plasma ALD
- Reduced flow ALD

USAGE

- Flat and 3D
- High aspect ratio
- Particles and powders

SUBSTRATE TYPE

- Up to 200mm wafers
- Up to 8 wafers batch

SUBSTRATE LOADING

- Ergonomically designed for manual loading

MAIN DIMENSIONS

- 1200 x 805 x 1630
- (L x W x H)

INTEGRATION

- All main components and electrical box integrated inside the tool frame

For product inquiries, please contact:
ald-sales@beneq.com